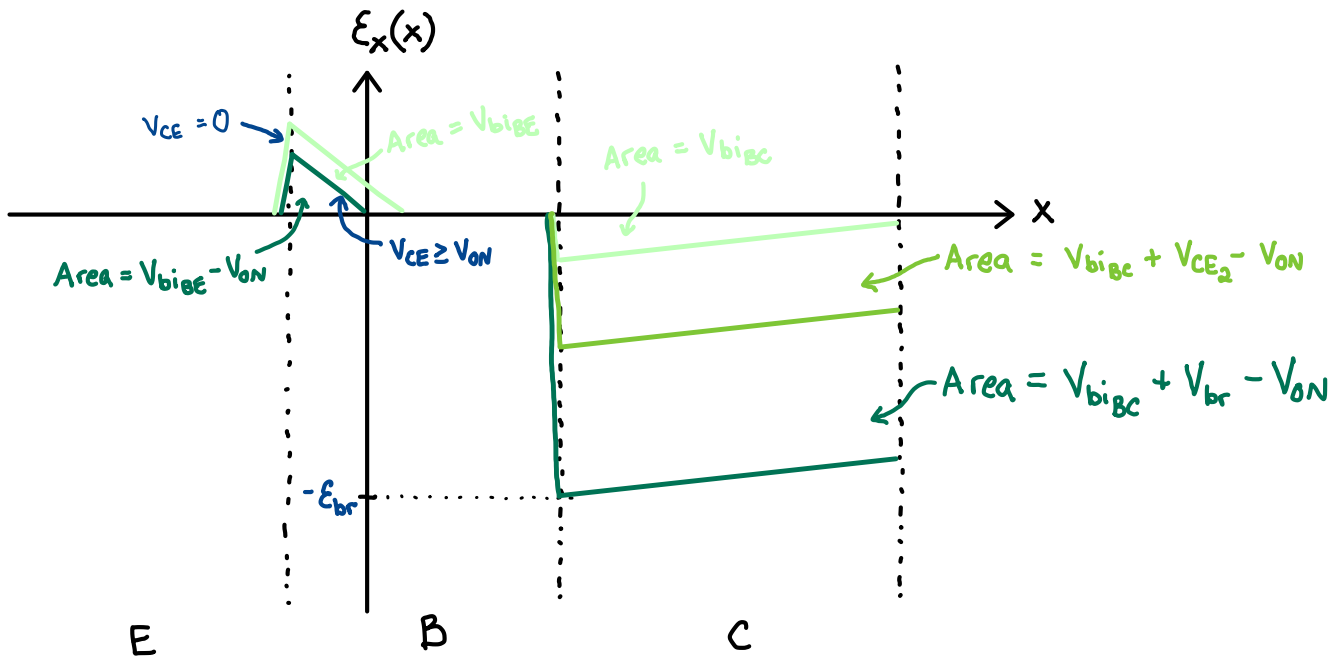
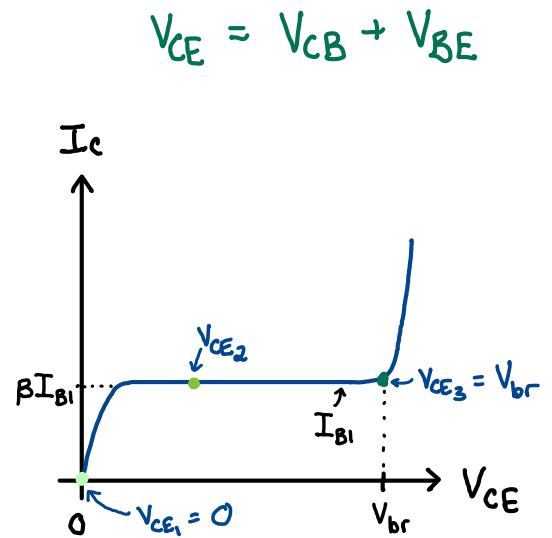
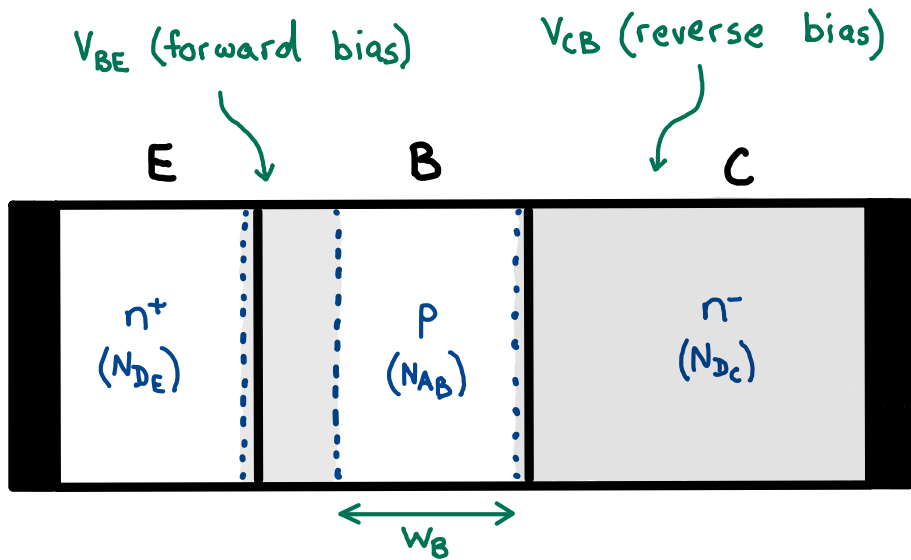
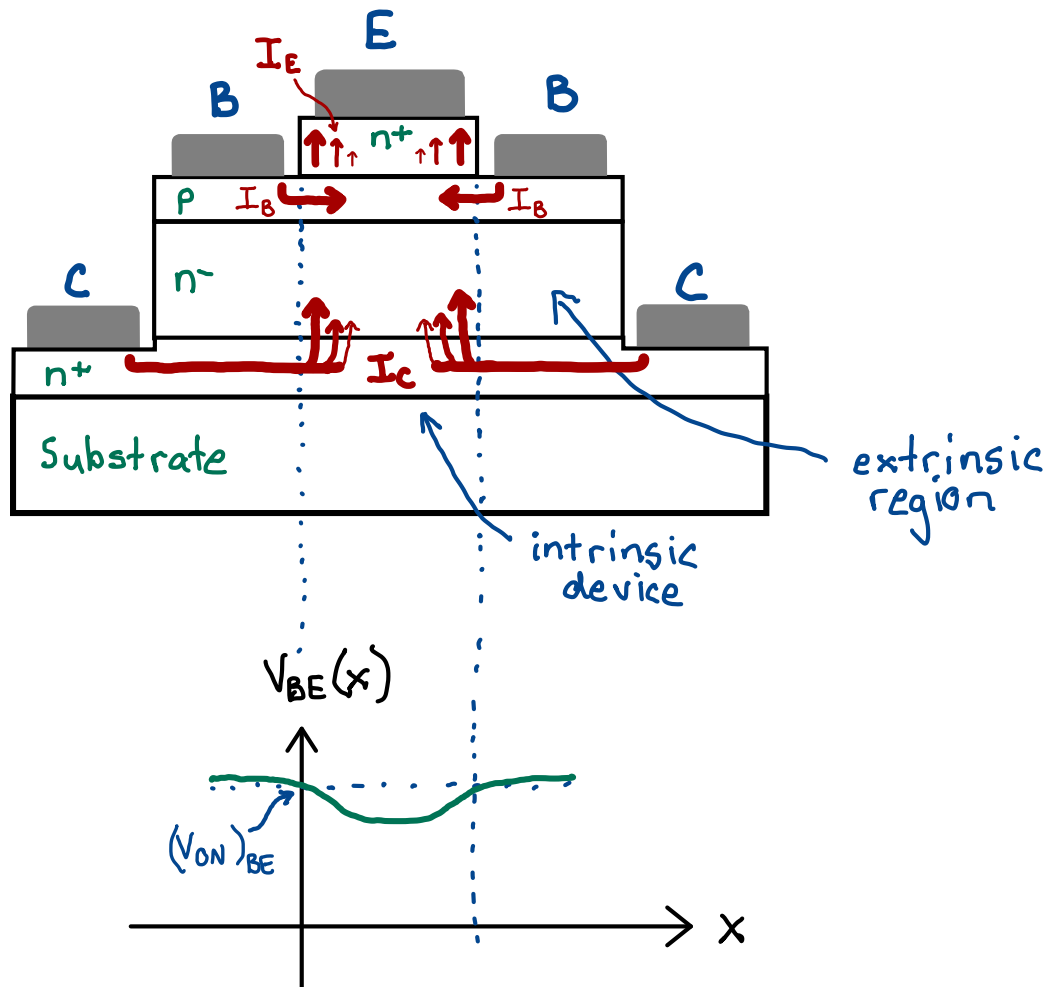


Breakdown in BJTs



Can you draw band diagrams for each of these 3 values of V_{CE} ?

Problems Encountered in this Device:



- Base resistance
 - Thin, moderately doped base
 - Separation between base contact and emitter mesa
- Current crowding
 - Thin, moderately doped base

Summary of BJT design parameters:

→ To maximize β :

- make W_B small

- make $N_{AB} \ll N_{DE}$

} Leads to large R_{base} and current crowding

→ To mitigate Early effect and increase V_{br} :

- make collector n^- and thick

Limited by RF parameters and Kirk Effect (to be discussed)

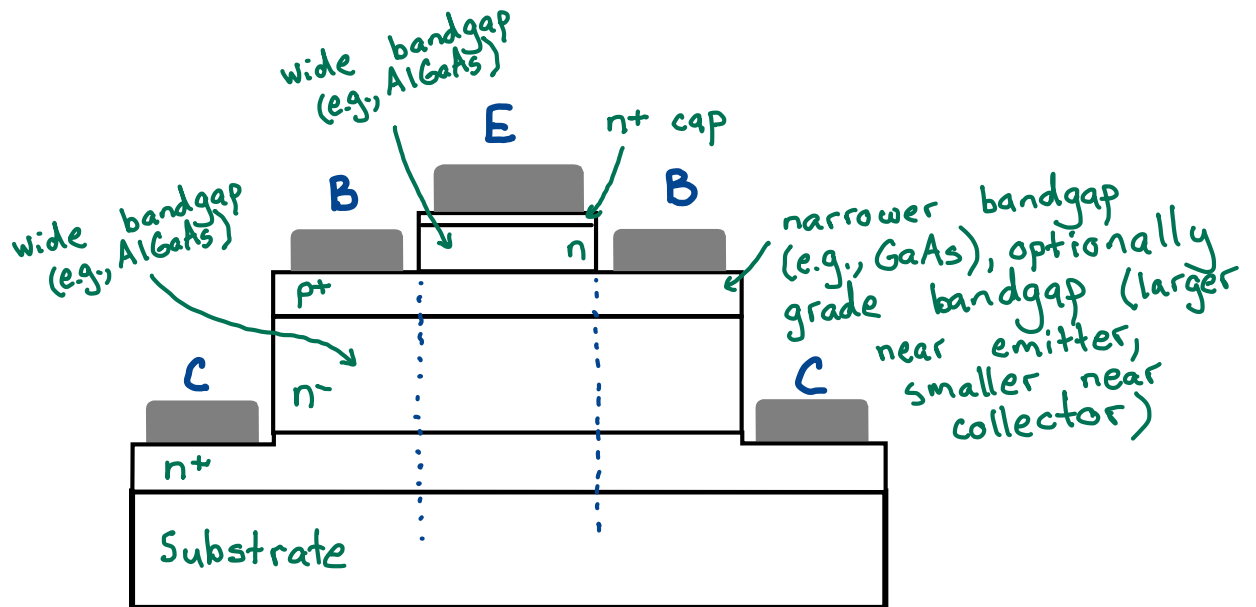
How do we address R_{base} and current crowding issues?

→ Device design

→ Processing techniques

(Different solutions for Si than for III-V semiconductors)

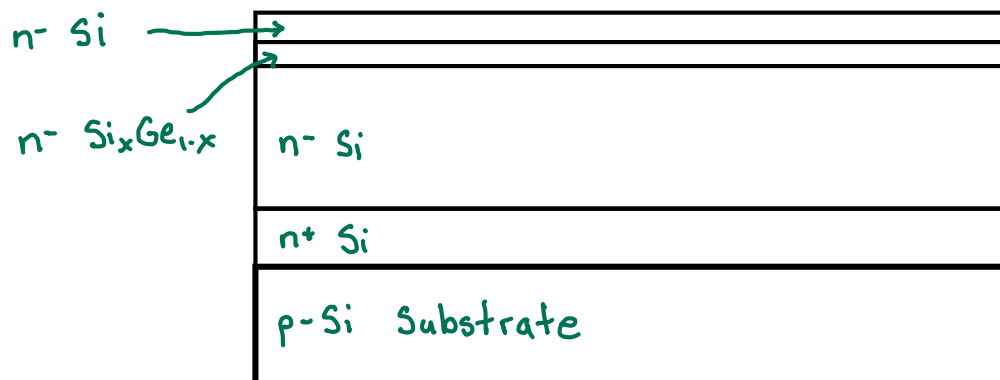
AlGaAs / GaAs DHBT:



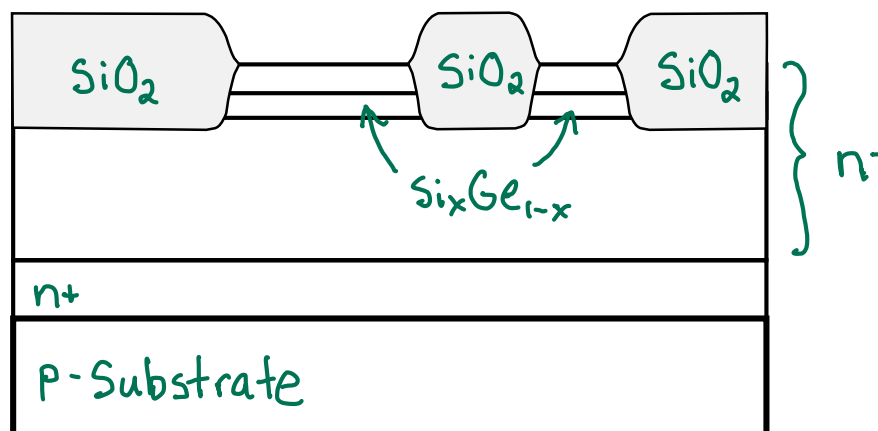
- Wide bandgap emitter allows high base doping (p^+) while maintaining α close to 1
- p^+ base reduces R_{base} and current crowding
- n^+ emitter cap maintains good emitter contact
- Wide bandgap collector increases breakdown voltage

Si Double Polysilicon HBT w/ self aligned emitter/base:

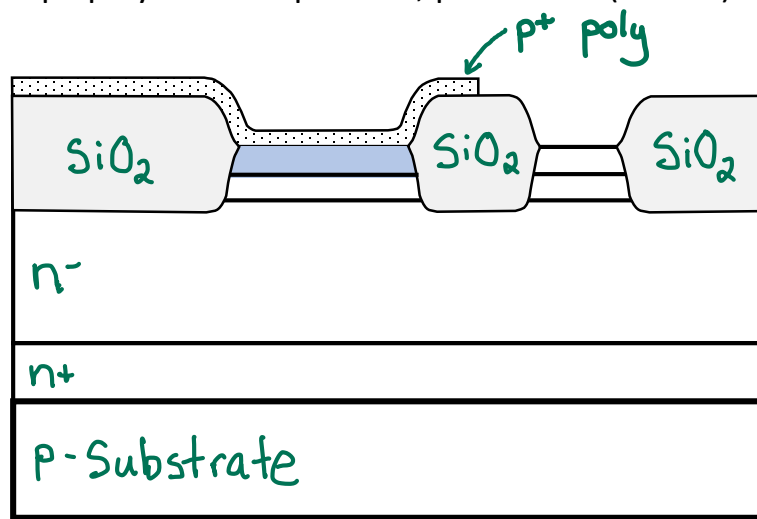
1. Epitaxial growth of material layers



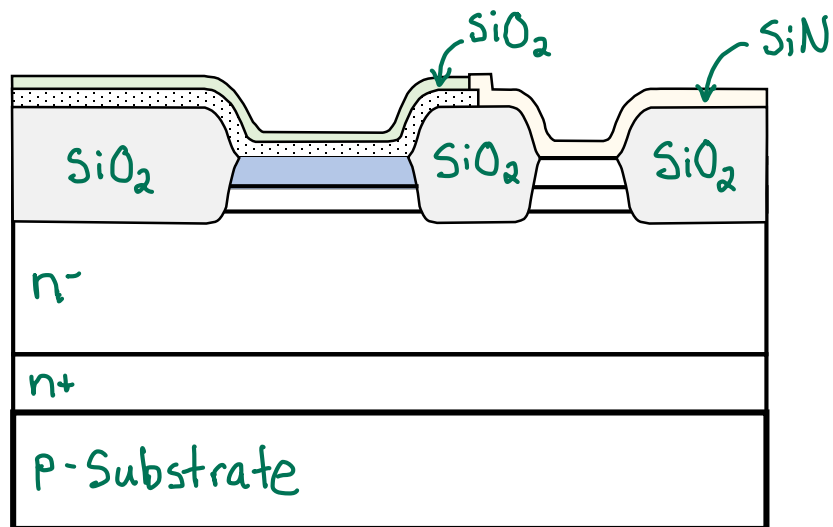
2. Local oxidation (LOCOS) of Si



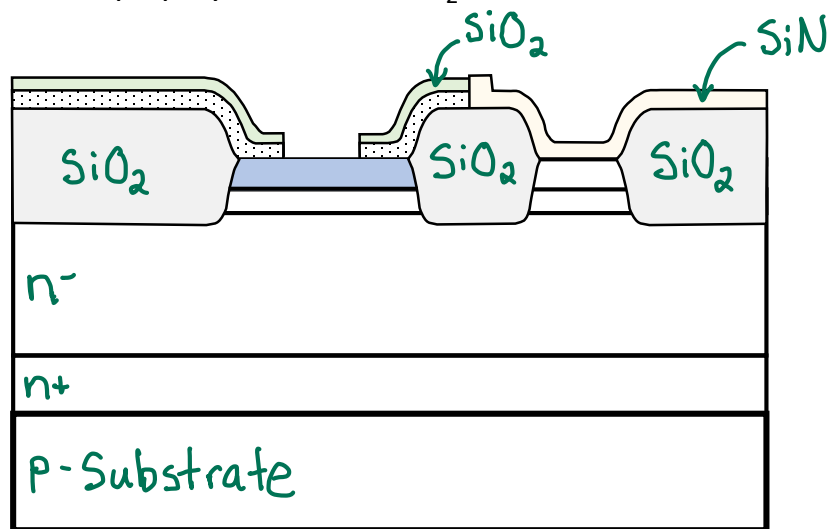
3. p+ polysilicon deposition, p-diffusion (anneal)



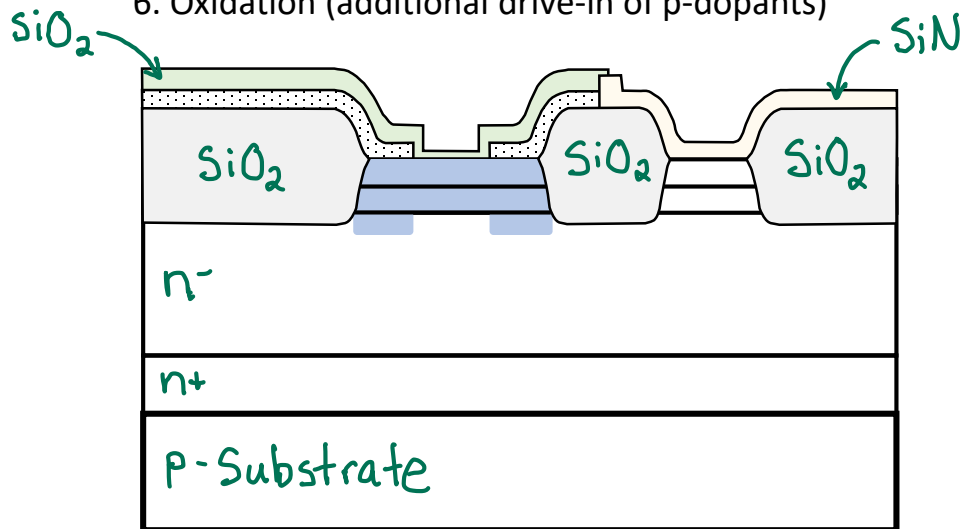
4. SiN mask, oxidation of p+ poly



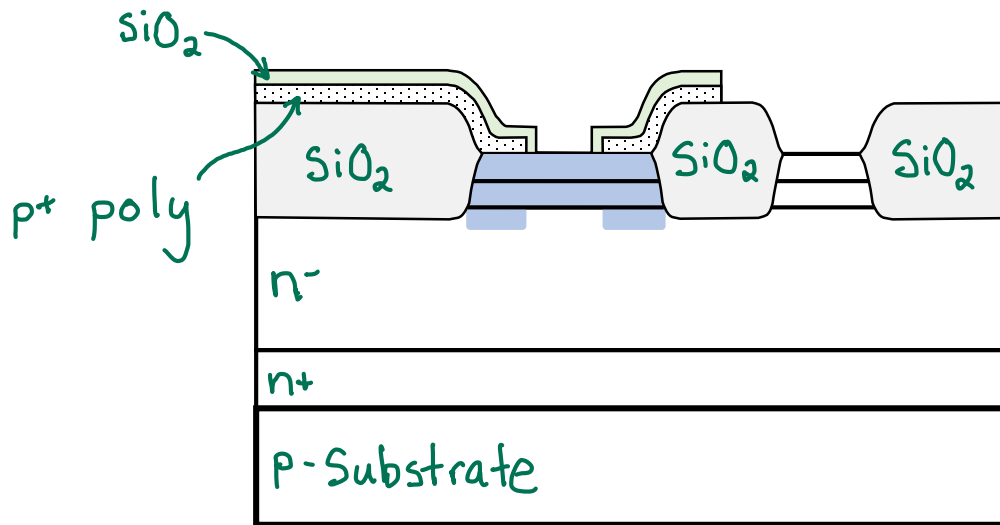
5. Etch p+ polysilicon and SiO_2



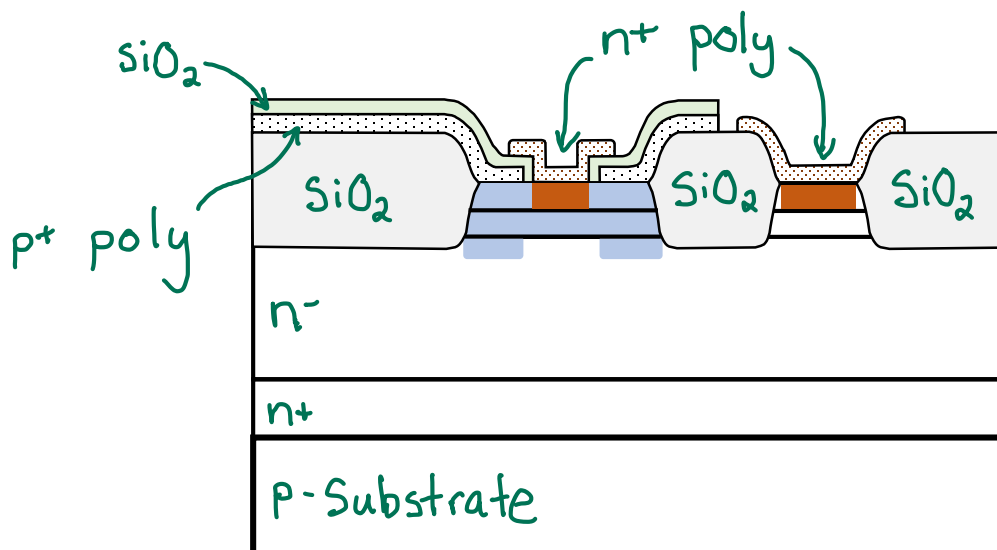
6. Oxidation (additional drive-in of p-dopants)



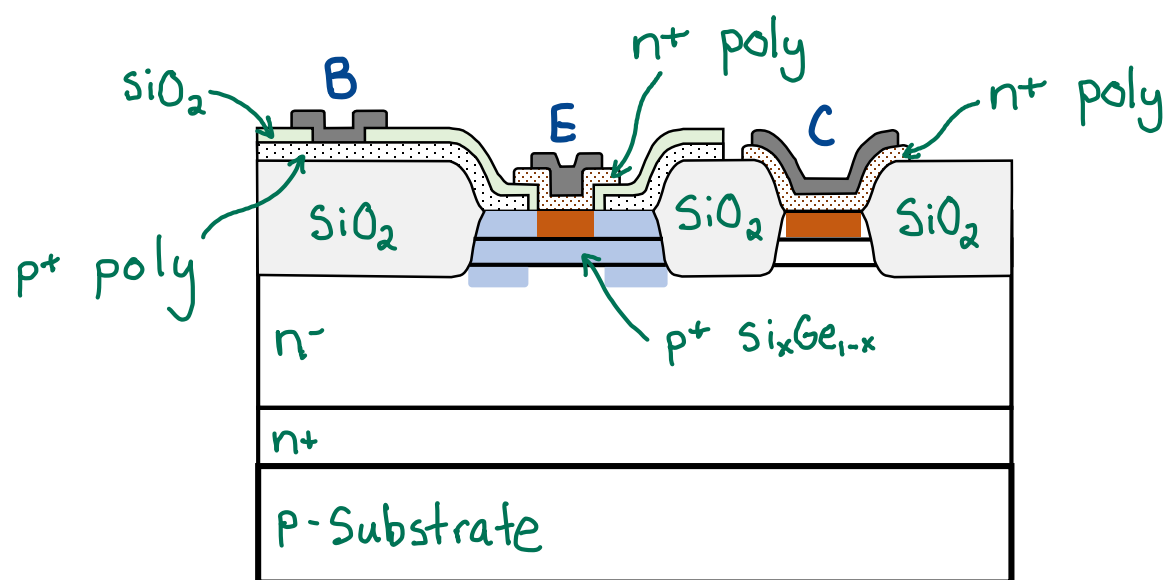
7. Anisotropic etch of SiO_2 , remove SiN



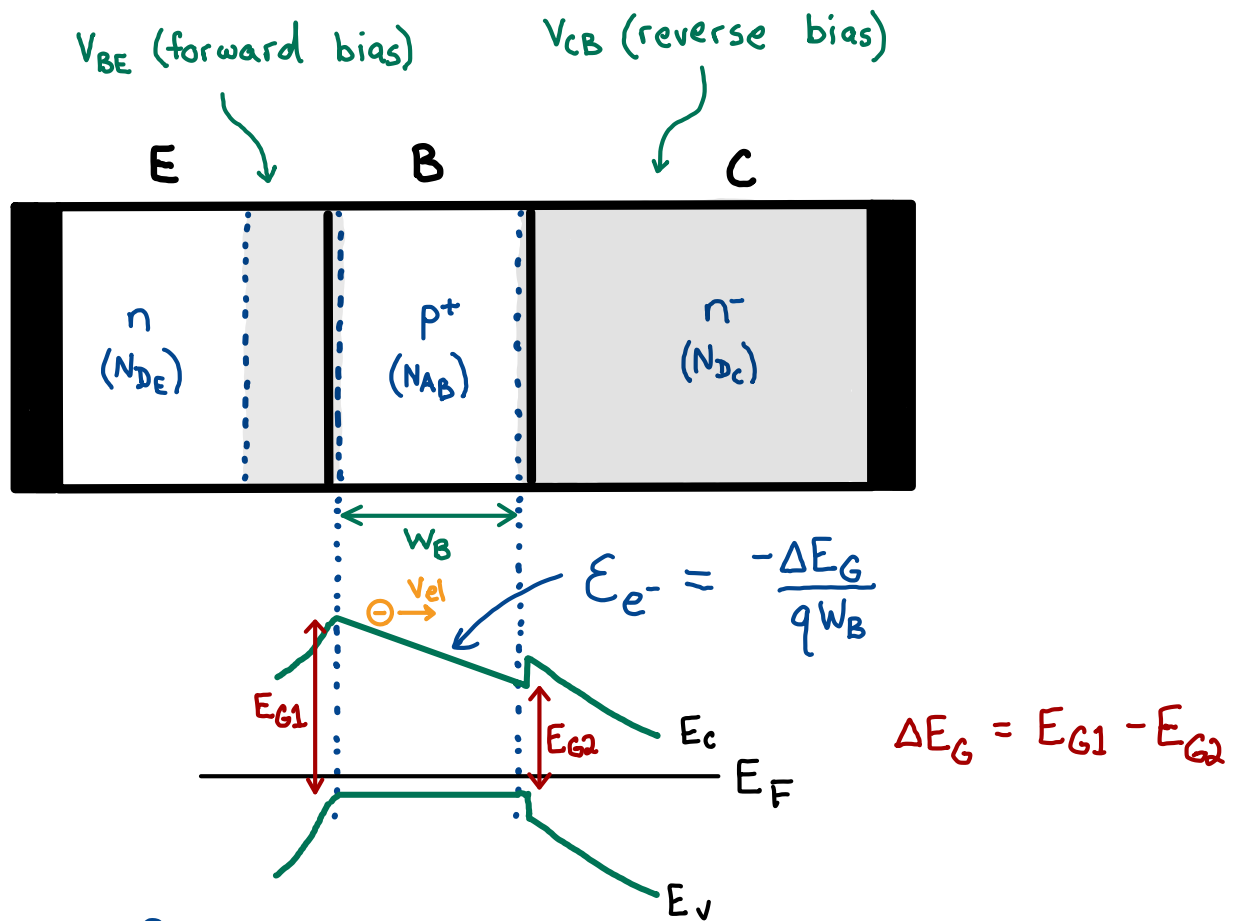
8. n+ polysilicon deposition, n-diffusion (anneal)



9. SiO₂ etch, deposit contacts



Graded Bandgap in the Base



- $V_{el} = \mu_n \mathcal{E}_{e^-}$
- Quasi $\mathcal{E}$ -field in base pulls e^- 's across base at a faster rate than diffusion rate, doesn't impact holes
- For the same value of V_{BE} , this increases J_{nE} by a factor $(\Delta E_G/kT)$, while J_{pE} and J_{rec} remain unchanged (see Muller/Kamins for derivation)
- Linear grade in base increases β by a factor $(\Delta E_G/kT)$